



Docket No. 50261-2

#516  
VB  
11/8/01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT: G. Taylor et al.  
SERIAL NO.: 09/330,418 EXAMINER: S. Lee  
FILED: June 11, 1999 GROUP: 1752  
FOR: NOVEL POLYMERS AND PHOTORESIST COMPOSITIONS

THE HONORABLE COMMISSIONER OF PATENTS AND TRADEMARKS  
WASHINGTON, DC 20231

SIR:

AMENDMENT

Applicants are in receipt of the Office Action dated June 20, 2000 for the above identified application. Please amend the application as follows.

RECEIVED  
JUN 27 2001  
TECHNICAL ROOM

IN THE CLAIMS

Please cancel claims 1-8 and 14-18 without prejudice.

Please add the following new claims.

19. A positive-acting photoresist composition comprising a photoacid generator compound and a polymer that is substantially free of aromatic groups and that comprises pendant acid-labile groups that contain an optionally substituted cycloalkyl group having 3 or 4 ring carbon atoms, or an optionally substituted alkenyl group.

20. A photoresist composition of claim 19 wherein the polymer comprises pendant acid-labile groups that contain an optionally substituted alkenyl group.